

DEPOSITION OF METAL FILMS  
ON MICROPARTICLES TRAPPED  
IN RF MAGNETRON DISCHARGE

*A.F. Pal, A.G. Rudavets, A.N. Ryabinkin,  
A.O. Serov*

Institute of Nuclear Physics,  
Lomonosov Moscow State University  
(1(2), Leninskie gory, GSP-1, Moscow 119991,  
Russian Federation; e-mail: aserov@mics.msu.su)

S u m m a r y

The technique for a metal film deposition on spherical microparticles in an RF plasma trap is presented. Both the particle confinement and the electrode sputtering are performed by a single RF magnetron discharge. The samples of a coated spheres are obtained and examined. The technique allows confining the particles near to the sputtered region close to the border zone of ballistic bombardment by sputtered atoms.